

**Abstract****Semiconductor wafer composed of monocrystalline silicon**

5 Semiconductor wafer of single-crystal silicon comprising a  
polished front side and a back side;  
a denuded zone which extends from the polished front side  
toward the back side to a depth of not less than 30  $\mu\text{m}$ ; and  
a region adjacent to the denuded zone and comprising BMD seeds  
10 which may be developed into BMDs, wherein a density of the BMDs  
at a distance of 120  $\mu\text{m}$  from the front side is not less than  $2 \times 10^8 \text{ cm}^{-3}$ .

Drawing relating to abstract: Fig.3